IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants:

Heng Liu

Title:

Chemical Vapor Deposition Reactor

received

CENTRAL PAY CENTER

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IN THE CLAIMS:

Claims 1-160.

cancelled.

Please add new claims 161-164 as follows:

- 161 (new) A chemical vapor deposition reactor system comprising:
 a plurality of chambers;
 a rotatable wafer carrier disposed within each of the chambers; and
 a common reactant gas supply configured to provide substantially the
 same gas mixture to each chamber.
- 162 (new) The chemical vapor deposition reactor system as recited in claim 161, further comprising a common gas exhaust system for the chambers.
- 163 (new) The chemical vapor deposition reactor system as recited in claim 161, wherein each chamber is a comparatively small chamber.
- 164 (new) The chemical vapor deposition reactor system as recited in claim 161, wherein each chamber defines a seven wafer reactor.

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